

ABSTRACT

The vacuum processing chambers 31 of the plasma processing units 3A and 3B are connected to the transfer chamber 2 and the wafer W in the positioned state is transferred from the transfer chamber 2 to the mounting stages 4 in the vacuum processing
5 chambers 31. The volume and length of the wave guide 5 are the same between the plasma processing units 3A and 3B. The location relationship of the wave guide 5 to the transfer directions M1 and M2 of the transfer arm 61 is the same between the plasma processing units 3A and 3B. As a result, the location
10 relationship of the wave guide 5 to the wafer W mounted on the mounting stage 4 in a predetermined direction is the same between the plasma processing units 3A and 3B.